In re: Lucovsky et al.

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On new page 35 following the claims, please insert the following:

## COMPLEX OXIDES FOR USE IN SEMICONDUCTOR DEVICES AND RELATED METHODS

## Abstract of the Disclosure

A semiconductor device includes a semiconductor substrate, a first oxide layer on the semiconductor substrate including an element from the semiconductor substrate, and a second oxide layer on the first oxide layer opposite the semiconductor substrate. The second oxide layer includes a stoichiometric, single-phase complex oxide represented by the formula:

 $A_hB_jO_k$ , or equivalently  $(A_mO_n)_a(B_qO_r)_b$ 

in which the elemental oxide components,  $(A_mO_n)$  and  $(B_qO_r)$  are combined so that h = j or, equivalently, ma = bq, and a, b, h, j, k, m, n, q and r are non-zero integers; and wherein:

A is an element of the lanthanide rare earth elements of the periodic table or the trivalent elements from cerium to lutetium; and

B is an element of the transition metal elements of groups IIIB, IVB or VB of the periodic table.